

PRESS RELEASE

Lasertec Corporation

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(Tokyo Stock Exchange Prime Market, Code 6920)

Lasertec Develops High-Brightness EUV Plasma Light Source

Yokohama, September 12, 2023- Lasertec Corporation announces that it has successfully developed a high-brightness EUV plasma light source named “URASHIMA” and that it will use the light source on its products.

Lasertec released the world's first actinic EUV patterned mask inspection system, ACTIS A150, in 2019. Today, A150 has been adopted among mask shops and wafer fabs around the world and recognized as an indispensable tool in the manufacturing and qualification of EUV masks for the production of leading-edge semiconductors. URASHIMA will be furnished on the ACTIS-series actinic EUV patterned inspection systems for further performance improvement.

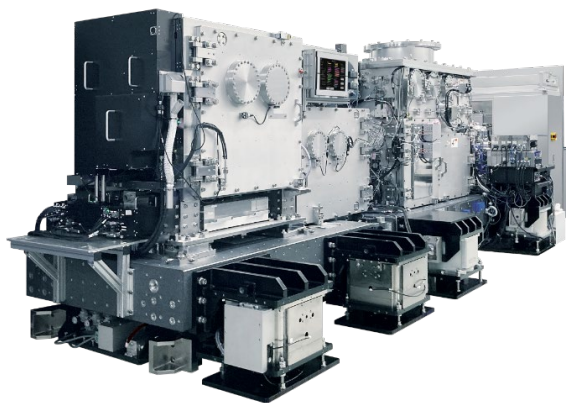
URASHIMA is a laser-produced-plasma (LPP) light source that produces EUV light by hitting laser pulses at liquified tin rotating at high speed. Its design is optimized for the ACTIS optics to minimize heat load and prevent damage on pellicles and to achieve high-brightness through-pellicle mask inspection.

One of the key challenges for a tin-based EUV light source is debris mitigation. URASHIMA is a debris-free light source that uses a Lasertec-proprietary debris mitigation system to prevent mask contamination. It also prevents the contamination of illumination optics and achieves higher productivity.

Lasertec is dedicated to developing unique solutions and contributing to the quality enhancement and productivity improvement of EUV lithography.

Applications

- Light source for the ACTIS Series Actinic EUV Patterned Mask Inspection System



URASHIMA High-Brightness EUV Plasma Light Source

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